

Resource Summary Report

Generated by [NIF](#) on Sep 21, 2026

Oxford: PlasmaPro 800 PECVD Plasma Technology

RRID:SCR_020379

Type: Tool

Proper Citation

Oxford: PlasmaPro 800 PECVD Plasma Technology (RRID:SCR_020379)

Resource Information

URL: <https://plasma.oxinst.com/products/pecvd/plasmapro-800-pecvd>

Proper Citation: Oxford: PlasmaPro 800 PECVD Plasma Technology (RRID:SCR_020379)

Description: PlasmaPro 800 offers solution for Plasma Enhanced Chemical Vapour Deposition processes on large wafer batches and 300mm wafers, in compact footprint, open loading system. Large wafer platen allows for production scale batch processing and 300mm wafer handling.

Resource Type: instrument resource

Keywords: Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

Availability: Commercially available

Resource Name: Oxford: PlasmaPro 800 PECVD Plasma Technology

Resource ID: SCR_020379

Alternate IDs: Model_Number_800_PECVD

Record Creation Time: 20220129T080350+0000

Record Last Update: 20260919T195434+0000

Ratings and Alerts

No rating or validation information has been found for Oxford: PlasmaPro 800 PECVD Plasma Technology.

No alerts have been found for Oxford: PlasmaPro 800 PECVD Plasma Technology.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We found 1 mentions in open access literature.

Listed below are recent publications. The full list is available at [NIF](#) .

He Q, et al. (2022) Low-loss ultrafast and nonvolatile all-optical switch enabled by all-dielectric phase change materials. iScience, 25(6), 104375.